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*Karen Cing-Mars 5/4/04*  
(Signature & date)

*MAY 3 6 2004*

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of May 04, 2004  
Bruce B. Doris, et al. : Group Art Unit: Not yet assigned  
Serial No.:10/709,314 Examiner: Not yet assigned  
Filed: 4/28/04 : International Business Machines Corporation  
2070 Route 52  
Hopewell Junction, NY 12533

**TITLE:** Method for Forming Narrow Gate Structures on Sidewalls of a Lithographically Defined Sacrificial Material

**INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to the duty of disclosure set forth in 37 C.F.R. 1.56, and further pursuant to the provisions of 37 C.F.R. 1.97 and 1.98, applicants hereby respectfully submit copies of the non-US patents and publications as listed on Form PTO-1449, attached hereto.

In citing these documents, no representation is made nor intended as to the pertinency or non-pertinency of the art, that better art than that listed is not available, or that other art is not applicable.

No fee is believed to be due for this submission. If any fees are required, however, the Commissioner is hereby authorized to charge such fees to Deposit Account No. 09-0458.

Respectfully submitted,  
Bruce B. Doris, et al.

By *Ira D. Blecker*  
Ira D. Blecker, Registration No. 29,894  
Telephone No. 845-894-2580

<b>INFORMATION DISCLOSURE CITATION</b> <small>(Use several sheets if necessary)</small>			ATTY DOCKET NO. <b>FIS920040036US1</b>		SERIAL NO. <b>10/709,314</b>			
			<b>BRUCE B. DORIS ET AL.</b>		<b>GROUP</b>			
<i>CIPR</i> <b>MAY 3 6 2004</b>			<b>U.S. PATENT DOCUMENTS</b>					
<b>*EXAMINER</b> <small>INITIAL</small>	<b>DOCUMENT NUMBER</b>	<b>DATE</b>	<b>NAME</b>	<b>CLASS</b>	<b>SUBCLASS</b>	<b>FILING DATE IF APPROPRIATE</b>		
<b>FOREIGN PATENT DOCUMENTS</b>								
		<b>DOCUMENT NUMBER</b>	<b>DATE</b>	<b>COUNTRY</b>	<b>CLASS</b>	<b>SUBCLASS</b>	<b>TRANSLATION</b> <small>YES      NO</small>	
<b>OTHER DOCUMENTS</b> <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>								
<small>1</small>	S. Deevi and Z. A. Munir; "The Mechanism of Synthesis of Titanium Nitride by Self-Sustaining Reactions;" Journal of Materials Research Society, Vo. 5, No. 10, October 1990; pages 2177 - 2183.							
<small>2</small>	J. Hartmann, W. ensinger, A. Koniger, B. Stritzker, and B. Rauschenbach; "Formation of Titanium Nitride Coatings by Nitrogen Plasma Immersion Ion Implantation of Evaporated Titanium Films;" Journal of American Vacuum Society Technology, A 14(6); November/December 1996; pages 3144 - 3146.							
<b>EXAMINER</b>				<b>DATE CONSIDERED</b>				
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>								

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<b>OTHER DOCUMENTS</b> <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>							
<b>9</b>		L. Dubois and R. Nuzzo; "The Decomposition of Silane and Germane on Ni(111): Implications for Heterogeneous Catalysis;" Surface Science 149; 1985; pages 133 - 145					
<b>10</b>		T. Abe, Y. G. Hong, M. Esashi; "Highly Selective Reactive-Ion Etching Using CO/NH <sub>3</sub> /Xe Gases for Microstructuring of Au, Pt, Cu, and 20% Fe-Ni;" Journal of Vacuum Science Technology, B21(5), Sept/Oct 2003; pages 2159 - 2162					
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*(Use several sheets if necessary)*

Docket Number (Optional)

**FIS920040036US1**

Application Number

**10/709,314**

Applicant(s)

**Bruce B. Doris et al.**

Filing Date

**4/28/04**

Group Art Unit

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**OTHER DOCUMENTS** *(Including Author, Title, Date, Pertinent Pages, Etc.)*

11

N. Matsui, K. Mashimo, A. Egami, A. Konishi, O. Okada, T. Tsukada; "Etching Characteristics of Magnetic Materials (Co, Fe, Ni) Using CO/NH<sub>3</sub> Gas Plasma for Hardening Mask Etching;" Vacuum 66, 2002; pages 479 - 485

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